

AMENDMENTS TO THE SPECIFICATION:

*Please delete the paragraph beginning at page 7, first full paragraph, which starts with "This object".*

*Please amend the first full paragraph between lines 4 and 15, at page 23:*

Furthermore, the above-mentioned object is achieved by providing an arrangement [for the implementation of the coating process according to one of Claims 10 to 26, the arrangement] comprising a vacuum chamber with a pumping system for generating a vacuum chamber, substrate holding devices for receiving the substrates to be coated, at least one gas supply unit for the metered addition of process gas, at least one vaporizer system for providing coating material for vapor depositing, an arc generating device for igniting a direct voltage low-voltage arc, a system for generating a substrate bias voltage, and at least one or several magnetic field generating devices for forming a magnetic far field.